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	Application No.	Applicant(s)	
	10/821,944	HAYASHIDA ET AL.	
Notice of Allowability	Examiner	Art Unit	
	David Nhu	2818	
The MAILING DATE of this communication appearance All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication GHTS. This application is subject to	olication. If not included will be mailed in due c	l ourse. THIS
1. X This communication is responsive to 9/9/05.			
2. The allowed claim(s) is/are <u>1-32</u> .			
 3. Acknowledgment is made of a claim for foreign priority ur a) All b) Some* c) None of the: 		1111. 276	
 Certified copies of the priority documents have 		0/114,376	
2. Certified copies of the priority documents have			
3. Copies of the certified copies of the priority do	cuments have been received in this i	national stage application	on from the
International Bureau (PCT Rule 17.2(a)).	•		
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requ	irements
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			TICE OF
5. CORRECTED DRAWINGS (as "replacement sheets") mus	t be submitted.		
(a) ☐ including changes required by the Notice of Draftspers		948) attached	
1) hereto or 2) to Paper No./Mail Date		,	
(b) ☐ including changes required by the attached Examiner's		ffice action of	
Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the			eack) of
 DEPOSIT OF and/or INFORMATION about the depo- attached Examiner's comment regarding REQUIREMENT 			ote the
Attachment(s)			
1. Notice of References Cited (PTO-892)	5. Notice of Informal P	atent Application (PTO	-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary		
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0	Paper No./Mail Dat 8), 7. Examiner's Amendn	e nent/Comment	
Paper No./Mail Date			
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. 🛛 Examiner's Stateme	ent of Reasons for Allow	/ance
	9. Other		
	Dec 8	F.	

Application/Control Number: 10/821,944 Page 2

Art Unit: 2818

REASONS FOR ALLOWANCE

- Claims 1-32 are allowed.
- 2. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests as cited in claims 1, 3, 5, 7, 8, 10, 13, 16, 17, 18, 19, 21, 24, 26, 29; an n-type GaN-based compound is formed on a substrate using ammonia as a raw material, characterized in that the ammonia is charged into a charging container so that at least a portion of the ammonia is in a liquid phase and in that the liquid phase ammonia has a water concentration of 0.01 to 0.5 vol. ppm. (as cited in claims 1, 3, 5, 8, 10, 13, 21, 24, 26); an n-type GaN-based compound is formed on a substrate using ammonia as a raw material, characterized in that the ammonia is charged in a gaseous state into reaction chamber housing therein the substrate so that at least a portion of the ammonia is in a liquid phase and in that the liquid phase ammonia has a water concentration of 0.01 to 0.5 vol. ppm as determined by FT-IR (as cited in claims 7, 16, 29); a GaN-based compound semiconductor, characterized by comprising a charging container and ammonia charged into the charging container so that at least a portion of the ammonia is in a liquid phase and characterized in t hat the liquid phase ammonia has a water concentration of 0.01 to 0.5 vol. ppm and in that the charging container is made of manganese steel or aluminum alloy; an inner surface subjected to plating treatment and polishing treatment; a cylindrical shape (as cited in claims 17, 18, 19). Applicants' undersigned representatives filed an amendment on 9/9/05, and also filed at that time a terminal disclaimer statement with reference to USP: 6,719,842 B2.
- 3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the

Application/Control Number: 10/821,944

Art Unit: 2818

issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons

for Allowance."

Conclusion

4. The prior art made of record and not relied upon is considered pertinent to applicant's

disclosure: Hayashida et al (6,719,842 B2): Ammonia for Use in Manufacturing of GAN-Type

Compound Semiconductor and Method for Manufacturing GA-Type Compound

Semiconductor.

5. Any inquiry concerning this communication on earlier communications from the examiner

should be directed to David Nhu, (571)272-1792. The examiner can normally be reached

on Monday-Friday from 7:30 AM to 5:00 PM.

The examiner's supervisor, David Nelms can be reached on (571)272-1787.

The fax phone number for the organization where this application or proceeding is assigned is

(703)872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should

be directed to the receptionist whose telephone number is (703) 308-0956

David Nhu

September 21, 2005

STUTE R.

Page 3

Replacement Sheet
U.S. Application No.: 10/821,944
Inventor: Hideki HAYASHIDA et al.
Group Art Unit: 2818 / Conf. No. 2372
Sheet 1 of 1

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